M. Jack J. M.

Via Express Mail Label #EL540189538US

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF: TSUTOMU YAMADA, ET AL.

FOR: DEPOSITION MASK AND MANUFACTURING METHOD THEREOF, AND

ELECTROLUMINESCENCE DISPLAY DEVICE AND MANUFACTURING

METHOD THEREOF

PRELIMINARY AMENDMENT

Box Patent Application
The Assistant Commissioner of
Patents and Trademarks
Washington, DC 02031

Sir:

(Typed or printed name of person mailing paper or fee)

(Signature of person mailing paper or fee)

Prior to the Examiner acting in the above-referenced application, please preliminary amend the abstract and claims as follows:

IN THE ABSTRACT:

Please amend the abstract as follows:

A single crystal or polycrystalline silicon substrate [(100)] is formed as a semiconductor substrate. Using a resist [(103)], an SiO_2 film [(101)] is formed as a first coating on at least part of the outer periphery of the substrate [(100)]. While using this SiO_2 film [(101)] as a mask, the substrate [(100)] is etched from the first surface side using KOH or the like. The thickness of the

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